

ABSTRACT

An in-line system having an overlay measurement function and a method thereof capable of reducing overlay measurement time and simplifying related jobs are disclosed.

The system for performing wafer processing comprises an in-line system comprising a

- 5 stepper for performing alignment and photo-exposure of a wafer and a spinner, in-line connected to the stepper, for performing coating and development of the wafer, and an overlay measurement device, in-line connected to the spinner, for automatically measuring an overlay accuracy of the wafer after wafer development is completed by the spinner.

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